

IN THE CLAIMS:

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1. *(currently amended)* A device comprising:
an array of electrostatically activated members formed in a layer comprising silicon; and
a substrate comprising a ceramic material and including conductors formed on a major surface thereof and in via holes formed therethrough, the conductors being positioned with respect to and separate from the silicon layer so as to selectively operate the array of members using an electrostatic force such that the includes of conductors on the silicon layer is not required.

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2. *(original)* The device according to claim 1 wherein the members are rotatable mirrors.

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3. *(previously amended)* The device according to claim 1 wherein the array comprises a structure of at least eight members by at least ten members.

4. *(currently amended)* The device according to claim 1 wherein the array is separated from the ceramic substrate by a spacer layer.

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5. *(original)* The device according to claim 1 further comprising a layer of metal on a major surface of the silicon layer.

6. *(original)* The device according to claim 2 wherein the mirrors are adapted to rotate about at least two axes.

7. *(currently amended)* The device according to claim 1 wherein the ceramic substrate comprises aluminum nitride (AlN).

8. *(original)* The device according to claim 1 wherein the substrate has a flatness of less than or equal to 10 microns.

9. *(original)* The device according to claim 1 wherein the substrate has a surface roughness of less than or equal to 1 micron.

10. *(original)* The device according to claim 1 wherein the conductors have a line width of less than 2 microns and a spacing less than 2 microns.

11. *(previously amended)* The device according to claim 1 wherein the conductors positioned to operate one member from the array of electrostatically activated members comprise an array of at least four conductors extending through separate via holes.

12. *(currently amended)* A device comprising:
 an array of at least 8x10 mirrors rotatable about at least two axes formed in a layer comprising silicon;
 a spacer layer formed over a surface of the silicon layer; and
 a substrate comprising a ceramic material ~~comprising AlN~~ having a flatness of less than or equal to 10 microns and a surface roughness of less than or equal to 1 micron, said substrate including conductors formed on a major surface thereof and in via holes formed therethrough, the conductors being positioned with respect to the silicon layer so as to selectively operate the array of mirrors using an electrostatic force, wherein the conductors remain separated from said silicon layer and are positioned to operate a mirror comprise an array of at least four conductors extending through separate via holes.

13. *(original)* A method of forming a device comprising:
 forming an array of electrostatically activated members in a layer of silicon; and
 mounting said silicon layer over a substrate comprising a ceramic material which includes conductors formed on a major surface of the substrate and in via holes formed in the substrate, the silicon layer being mounted so as to position the members with respect to the conductors to permit selective operation of the members.

14. *(original)* The method according to claim 13 wherein the members are movable mirrors.

15. *(original)* The method according to claim 13 wherein the silicon layer is mounted using an epoxy bond.

16. *(original)* The method according to claim 13 wherein the silicon layer is mounted using a solder bond.

17. *(original)* The method according to claim 13 wherein a spacer layer is included between the silicon layer and the ceramic substrate.
